

## Fabrication Of Cuprous Oxide Homojunction Solar Cell By Varying The Lactic Acid Ion Concentration Of Thin Film p-Cu<sub>2</sub>O Deposition Bath

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In this study, we have investigated the possibility of improving the  $V_{OC}$ , FF and  $\eta$  values of Cu<sub>2</sub>O solar cells while preserving the resulted high  $J_{SC}$  values. Here we report that controlling the growth of p-Cu<sub>2</sub>O by varying the lactic acid ion concentration of thin film p-Cu<sub>2</sub>O deposition bath has improved the performance of Cu<sub>2</sub>O homojunction solar cell while preserving high  $J_{SC}$  value. The fabricated surface treated thin film p-n homojunction solar cell has resulted  $J_{SC} = 12.95 \text{ mA cm}^{-2}$ ,  $V_{OC} = 445 \text{ mV}$ ,  $FF = 39.5\%$  and  $\eta = 2.28\%$ . The efficiency reported here is very significant in respect of Cu<sub>2</sub>O homojunction solar cells because it clearly demonstrates the possibility of adapting the low cost Cu<sub>2</sub>O material and fabrication methods in achieving a commercially viable solar cell.

### Introduction

Cuprous oxide (Cu<sub>2</sub>O) is known to be the oldest low-cost, environmentally friendly lattice defect type semiconducting solar energy material (1). For decades its optoelectronic properties have intrigued PV community to investigate on development of Cu<sub>2</sub>O based solar cells (2–6). Of course, development of thin film Cu<sub>2</sub>O solar cells could provide affordable solar cells to the tropical rural communities to benefit cost-free electricity.

TABLE I: Reported performance of Cu<sub>2</sub>O homojunction solar cells; open circuit voltage ( $V_{OC}$ ), short circuit current density ( $J_{SC}$ ), fill factor (FF) and power conversion efficiency ( $\eta$ )

$V_{OC}$ (mV)	$J_{SC}$ (mA cm <sup>-2</sup> )	FF (%)	$\eta$ (%)	Reference
287	12.4	25	0.89	(7)
423	2.5	27	0.29	(8)
490	12.8	NR*	2.64	(9)
420	2.68	38	0.42	(10)
621	4.07	42	1.06	(11)
324	12.67	30.7	1.3	(12)
320	1.23	35	0.102	(13)
120	3.97	23	0.104	(14)

\*NR – Not Reported

Thin film Cu<sub>2</sub>O can be synthesized easily using method of electrodeposition. Electrodeposited thin film Cu<sub>2</sub>O will exhibit n- or p-type conductivity based on the deposition parameters as well as annealing conditions (15–18). In principle, fabrication of